

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s): Wang	
Application No.: 10/723,746	Art Unit: 1765
Filed: 11/25/2003	Examiner: L. Umez Eronini
Title: POLISHING COMPOSITION FOR CMP HAVING ABRASIVE PARTICLES	
<u>Attorney Docket No.: 03049US</u>	

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Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

RESPONSE

Dear Sir:

In response to the Office Action of December 22, 2005, having a shortened statutory deadline of March 22, 2006, please amend this application as follows:

Do Not Enter  
Amendment.  
L.T.M-E  
3/25/2006